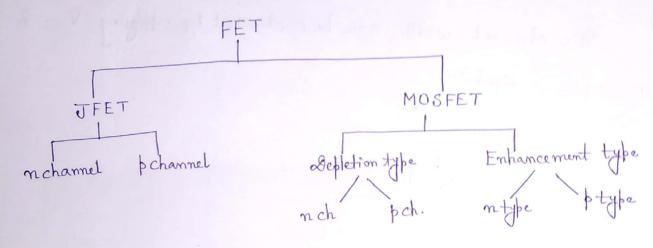
Field Effect Transistor (FET)

FET is a three terminal device in which the output current flow through the device is controlled by the applied electric field between two terminals.

is controlled by applied field it is called FET.

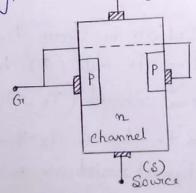
· Current flow through the device is due to majority cornier (for n channel is e, and for p channel is h) only, so this dear device is called unipolar device.



N channel JFET:

Construction:

No channel JFET is a netype Si bar (uniformly doped). The bar has of the two ends, two doped). The bar has of the bar with heavily doped terminals are called Source and Drain. In type bar is terminals are called Swo sides of the bar with heavily doped very lightly doped. Two sides of the bar with heavily doped with parts are with parts are impurities. Vanious parts are with parts are



The various parts are -

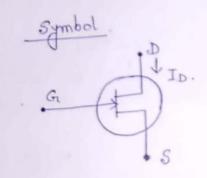
Source (8): - The source is the terminal through which the majority carrier enters into the bare.

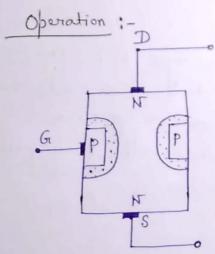
Gate (G): - Two terminals from & sugions are shorted and this common terminal is called Grate.

Anain (D): - Drain is the terminal through which the majority carrier leaves the bar.

Channel: - The region between of S and D which is some Sandwid Soundwitched between two & regions is called channel.

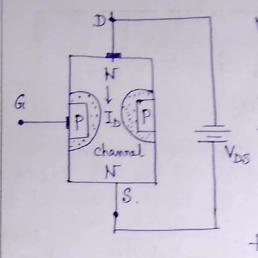
This channel width can be controlled by applying Vois & VDS.





(i) when neither any bias is applied to the gate (VGS=0) non any voltage to the drain w. n to source (VDS=0) the depletion regions around the P-N junctions are of equal thickness and symmetrical.

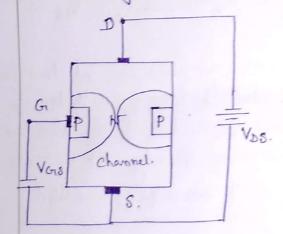
(ii) When positive voltage is applied to the drain terminal (D) w. or to Source (S) without connecting the Grate (G) to supply, electrons flow from S to D and drain current (ID) flows through the channel from D to S. Due to flow of ID there is a uniform voltage drop across the channel resistance as we move from D to S.



The gate is more regative with respect to those points in the channel which are nearer to (D) than to (S) So depletion.

You layor functivate more deeply into the channel at points lying closer to D than to S, so wedge - Shaped depletion regions are formed.

The Size of the depletion boyon formed determines the width of the channel and the magnitude of the awount (ID) flowing through the channel.

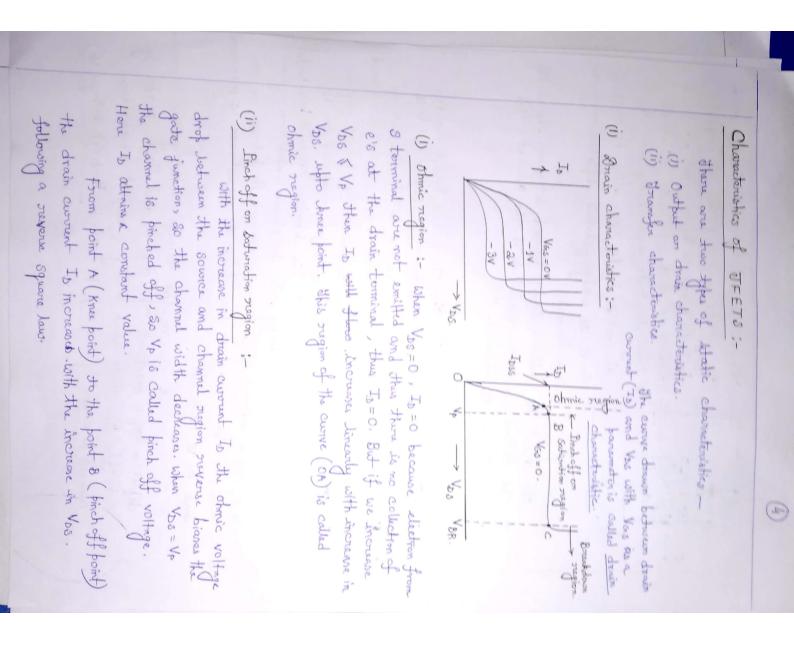


(111) When the gate is biased regative with suspect to the source while the drain is positive were to the source,

P-N junctions are reverse biased and depletion regions are formed. I sugious are heavily doped compared to N channel, so depletion channel benefite deeply into the channel deepletion sugion

is a region depleted of the charge coverier, it behaves as an insulator. The channel is marviowed, the resistance is increased and ID is reduced.

If the negative voltage at the gate is increased depletion layous meet at the centre and ID is completely cut off. The Grate Source voltage (VGs) at which drain award is completely cut off is called linch off voltage (Vp).



The region of the characteristic curve in which drain current (ID) remains almost constant is called pinch off region. It is the normal operating region of the JFET used as an amplifier. The drain current in the binch off with 45. Vois =0 is referred to the drain source soluration current (IDSS).

Drain current in the pinch off oregion is given by Set Shockley's equation.

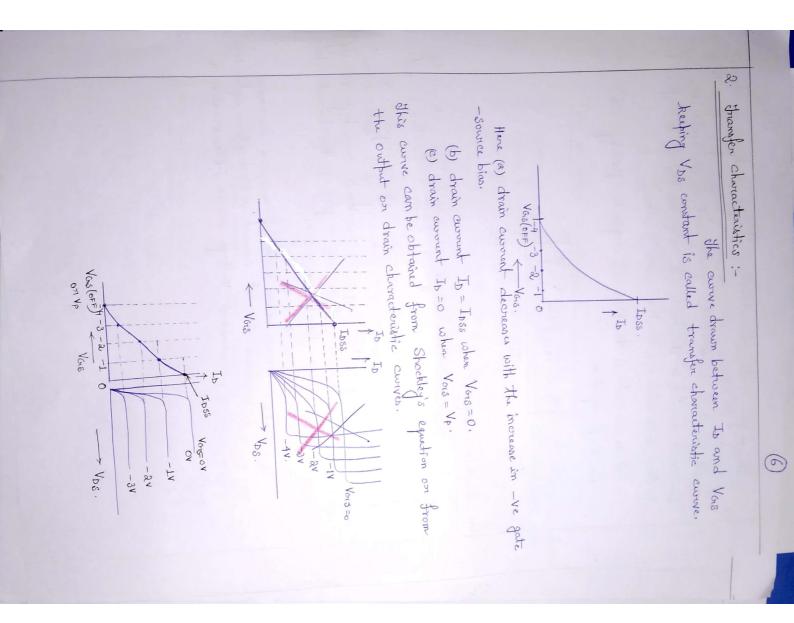
$$\boxed{I_D = I_{DSS} \left(1 - \frac{V_{G1S}}{V_P}\right)^2}$$

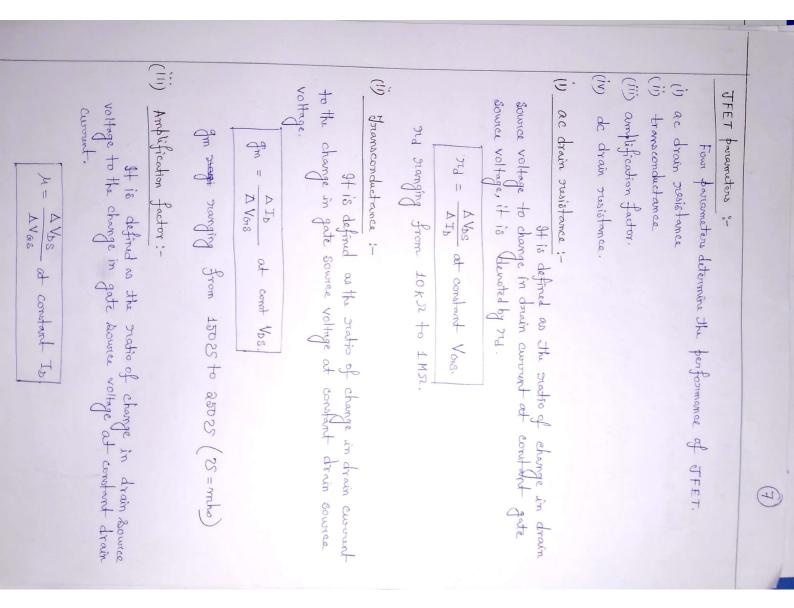
$$= I_{DSS} \left(1 - \frac{V_{G1S}}{V_{G1S}(OFF)}\right)^2$$

iii) Breakdown Region:-

increased a stage comes when the gate channel junction breakdown. At this point the drain current increases very rapidly and. This happens because the charge coveriers making up the saturation current at the gate channel junction accelerate to a high velocity and produce an avalanche effect. This region of the characteristic curve (CD) is called Breakdown region.

Sio JFET behaves as an ordinary rusiston in ohmic region, as a constant current source in binch off or saturation region and as a constant voltage source in the breakdown region.





Amplification factor (4) of JFET indicates how much more control the gate Source Voltage has over drain current in comparison to the drain source voltage.

$$\mathcal{L} = \frac{\Delta V_{DS}}{\Delta V_{GIS}} = \frac{\Delta V_{DS}}{\Delta I_D} \times \frac{\Delta I_D}{\Delta V_{GIS}}$$

$$\mathcal{L} = \mathcal{T}_{UX} g_{m}$$

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